

<p>Optical frequency generation (SFG/DFG) $\omega = \omega_1 \pm \omega_2$ Optical parametric amplification/oscillation (OPA/OPG) $\omega = \omega_1 \pm \omega_2$ Optical Kerr effect/quadratic Pockels effect $\Delta n(\omega) \propto \chi^{(2)}$ Third harmonic generation (THG) $\omega = 3\omega_1$ Four wave mixing (FWM) $\omega = \omega_1 \pm \omega_2 \pm \omega_3$ Two photon absorption (TPA) $\rightarrow 2\omega_{ph}$ Stimulated Raman/Brillouin scattering (SRS/SBS) Methodology for nonlinear</p> <p>Weyl expression for electric field in medium: $E = Re[E_0 U(\omega, t)] \propto \exp(ik \cdot z - i\omega t + t)] \propto \exp(ik \cdot z - i\omega t + t)] + c.c.$ Calculate the linear and nonlinear polarization: $P = \epsilon_0 \chi^{(1)} E + \chi^{(2)} E^2 + \chi^{(3)} E^3 + \dots = P_L + P_{NL}$ Substitute in to the electromagnetic wave equation: $\Delta E = \mu_0 \frac{d^2 P}{dt^2} (\epsilon_0 E + E) = \mu_0 \epsilon_0 \frac{d^2 E}{dt^2} + \mu_0 \frac{d^2 P_{NL}}{dt^2}$ (Source Term) Second harmonic generation: $P_{NL} = \chi^{(2)} E^2 \propto \chi^{(2)} Re[E]^2 \exp(2i\omega_1 t)$</p> <p>Optical Kerr effect: Third harmonic generation (THG) 3rd Order Optical Nonlinear effects: Total electric field $E = E_{light} = Re[E_0 \exp(i\omega t)]$ Consider the ω term $\epsilon_0 E_0 ^2 = E_0^2 \epsilon_0 \Delta n = n_2 I_0 \times I_0 \rightarrow$ Change of the imaginary part of non-linear index: two photon absorption Third harmonic generation $P_{NL} = \chi^{(3)} E^3 \propto \chi^{(3)} Re[E]^3 \exp(3\omega t)$ Consider the 3ω term Interaction of photons with phonons: photon-phonon</p> <p>= Stokes line, Photon + Phonon = anti-Stokes line When the virtual levels aligns with a real energy level Significant enhancement of Raman scattering Pockels effect / Electro-optic (EO) effect Total electric field: $E = E_{light} + E_{EO} = Re[E_0 \exp(i\omega t)] + E_{EO} = \frac{1}{2} E_0 \exp(i\omega t) + c.c. + E_{EO}$ Use (a+b)² = a² + 2ab + b² $P_{NL} = \chi^{(3)} [Re[E_0 \exp(i\omega t)] + 2E_{EO} \exp(i\omega t)]^2 = \chi^{(3)} [E_0^2 \exp(2i\omega t) + 4E_0 E_{EO} \exp(i\omega t) + 4E_{EO}^2 \exp(i\omega t)]$</p> <p>$\propto \chi^{(3)} [E_0^2 \exp(2i\omega t) + 4E_0 E_{EO} \exp(i\omega t) + 4E_{EO}^2 \exp(i\omega t)]$ [polarization oscillating at the optical frequency] $\propto \chi^{(3)} [E_0^2 \exp(2i\omega t) + 4E_0 E_{EO} \exp(i\omega t) + 4E_{EO}^2 \exp(i\omega t)]$ [$E_0 \ll c \times \Delta n$] electrostatic constant change due to two photon nonlinearity Gate: Optical, Source-Drain Electrical: Photo-Transistor Gate: Optical, Source-Drain Electrical: Photo-Transistor Gate: Electrical, Source-Drain Electrical: Photo-Field-Effect Transistor Gate: Electrical, Source-Drain Optical: Photo-Transistor</p> <p>\rightarrow Electro-Optic Modulator Electro-optic Modulation Modulator via Modulator and Modulator via Laser Modulation Mechanisms $\Delta V \rightarrow \Delta n_{eff}$ goes to Pockels $\approx rE$, Kerr $\approx (AK)^2 E$, Franz-Keldysh and QCSE, Free Carriers $\approx \Delta n_{carrier}$ Types of Modulation Δn Electro-refractive Effect ("EO") phase Δn (e.g. MZI) Δk: electrooptic-absorption(EA) \rightarrow absorption $\Delta \alpha \propto$ (e.g. linear) Electro-Optic Modulation Mechanisms</p>	
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E-Field: Franz-Keldysh, Bulk Material E-Field + Excitons: Quantum-Confined-Stark-Effect (QCSE), Quantum well dots Excitons = bounds e^-/h^+ pair Carrier-based, Plasma-effect (for SU) EAM Performance Vectors Switching Energy: $U_{sw} = \frac{1}{2} Q_{sw} V_{sw} \approx 1.94 \times 10^{10} \frac{Q_{sw}}{eV} f_{sw}^2 \left(\frac{h\nu_{ph}}{2\pi} \right)^2 \left(\frac{d_{sw}}{nm} \right)^{-1}$	2D Materials = strong Absorption	Dimensions \rightarrow ↓ Coulomb Screening \rightarrow ↑ High Exciton Binding Energy \rightarrow ↑ α
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Charge-driven Materials for EO Modulation, Low Broadening (γ) Improves Performance | EAM Performance Parameters, | Switching Charge: $Q_w = 2.2\epsilon_0 W n_{eff} / \sigma_{eff} \omega_1 (\approx 6.23 \times 10^{15} \text{ cm}^{-2} \frac{\text{C}}{\text{m}^2})$ | Effective Thickness $S_{eff} = W n_{eff}$ | Capacitance: $C_{eff} = \epsilon_0 \epsilon_r W L / d_{oe} = \frac{2.2\epsilon_0 \epsilon_r W n_{eff} L}{\sigma_{eff} \omega_1}$ | Switching Voltage: $V_{sw} = Q_{sw} / C_{eff} \approx 6.23 \times 10^{15} \text{ cm}^{-2} \frac{\text{C}}{\text{m}^2} \frac{\sigma_{eff} \omega_1}{2.2\epsilon_0 \epsilon_r W n_{eff} L} (\frac{\text{V}}{\text{cm}}) \approx 1.4 \times 10^4 \frac{\text{V}}{\text{cm}}$

$$\begin{aligned}
 & \text{switching Energy: } Q_{\text{sw}} = Q_{\text{sw,low}} + 1.94 \times 10^{-16} \left(\frac{f_{\text{sw}}}{\text{MHz}} \right)^2 \left(\frac{V_{\text{DD}}}{\text{V}} \right)^2 \quad \text{5-bit Cell Turn-on Delay: } \tau_{\text{on}} = 1.2 \times 10^{-16} \left(\frac{f_{\text{sw}}}{\text{MHz}} \right)^2 \left(\frac{V_{\text{DD}}}{\text{V}} \right)^2 \quad \text{Energy Dissipation Rate (Contrast Ratio): } E_{\text{Diss}} = 1.44 \times 10^{-16} \left(\frac{f_{\text{sw}}}{\text{MHz}} \right)^2 \left(\frac{V_{\text{DD}}}{\text{V}} \right)^2 \quad \text{Modulation Characteristics: Contrast Ratio: } \frac{P_{\text{max}}(V_{\text{off}})}{P_{\text{min}}(V_{\text{off}})} \quad \text{Insertion Loss: } L_{\text{loss}} = \frac{P_{\text{in}}(V_{\text{off}})}{P_{\text{out}}(V_{\text{off}})} \quad \text{Modulation Efficiency: } \eta = 1 - e^{-\frac{P_{\text{max}}(V_{\text{off}})}{P_{\text{min}}(V_{\text{off}})}} \\
 & \text{(FOM) Metric: } BW_{\text{FOM}} = \left(\frac{1}{\tau_{\text{on}}} \right) \left(\frac{1}{\text{modulation depth}} \right) \quad \text{Phase(Interface) Modulator: } P_{\text{FOM}} = P_{\text{max}} \cos^2 \left(\frac{\Delta V}{V_{\text{DD}}} \right) \quad \Delta P = \frac{1}{2} \left(P_{\text{max}} - P_{\text{min}} \right) \quad \text{Insertion Loss: } L_{\text{loss}} = \frac{P_{\text{in}}(V_{\text{off}})}{P_{\text{out}}(V_{\text{off}})} = 1 - e^{-\frac{P_{\text{max}}(V_{\text{off}})}{P_{\text{min}}(V_{\text{off}})}} \quad \text{Phase(Interface) Modulator: } \Delta T = P_{\text{max}}(V_{\text{off}}) - P_{\text{min}}(V_{\text{off}}) \quad \text{Optimize Modulation: } \frac{\Delta T}{P_{\text{max}}(V_{\text{off}})} = 0.9
 \end{aligned}$$

$L_{\text{range}} = \frac{1}{k} \ln \left(\frac{2\pi}{k} + 1 \right)$ Detailed Look: Franz-Keldysh Effect (EA): Oscillations in above bandgap absorption (due to electron standing wave), Below band gap absorption (due to evanescent tails of wavefunction) Applied Voltage: Electrostatics of pn Junction Electric field at quantum well: 2nd order perturbation theory Change in energy level (DOS): 1st order perturbation theory QCSDE Advantages more modulation: w/V_{bi}

<p> $\hbar^2 \kappa^2 / m^*$ better confined → Stronger Exciton Binding energy Typical Structure = Quantum Well </p>	<p> Summary Schawlow-Towns Limit: $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ Schawlow-Towns Limit* $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ $\Delta \nu_{laser} = \frac{\pi \hbar \omega (\Delta \omega_{exciton})^2}{4 E}$ Lasers by Cavity Type, Fabry-Perot, Vertical Surface Emitting Lasers = VCSEL, Distributed </p>
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Bragg Reflector = DBR, Distributed Feedback = **DFB** **Summary NL optics EOM** $E_{avg,dist,avg} = \frac{1}{2} C_V^2 \epsilon_{\text{line}}$ $\left(\frac{1}{2} \left(\frac{\omega}{c} \right) (\partial)^2 E^2_{\text{critical}} = \frac{1}{2} \epsilon \cdot E^2_{\text{critical}} \right) (WL D = \frac{1}{2} \epsilon \cdot E^2_{\text{critical}} \cdot (Volume)) D = e_0 E + P$ $P = e_0 \chi \cdot E^2 + \chi^{(2)} \cdot E^2 + \chi^{(3)} \cdot E^3 + \dots$ (From 2 on, Nonlinear Polarization) $= P_L + P_{NL}$ $\frac{E_{avg,dist,avg}}{2n_0 P_{NL}} = \frac{Q_1}{2n_0 P_{NL}} = \frac{1}{2} \frac{\Delta n_{avg}}{n_0} = \frac{1}{2} F$ $F_{\text{dist-average}} = \frac{1}{2} F$ $Q_{\text{dist-average}} = \frac{1}{4} V Q_{\text{total}}$ $\frac{\Delta n_{avg}}{n_0} = \frac{\Delta n_{\text{max}} \cdot \text{Length}}{n_0 \cdot \text{Length} \cdot \text{Modulation}} = \frac{\Delta n_{\text{max}}}{n_0 \cdot \text{Modulation}}$ **Modulation Characteristics: Contrast ratio**

$\eta_{\text{ext}} = \frac{P_{\text{out}}}{P_{\text{in}}}$	Insertion loss: $L_{\text{oss}} = \frac{P_{\text{in}} - P_{\text{out}}}{P_{\text{in}}}$ (Vols)	Modulation efficiency	Photodetector	CCD Coupled Devices (CCD), Integrated Photo-receiver(Rx)	Devices work by: Semiconductor absorbs light, Photodetector Separates e^-/h^+ generated by absorption, Space charge to perform work or drive a current	Recombination-Generation
Generation Band-to-Band, Recomb. Impact Ionization						
Recombination Direct, Rec. Auger, Excess Carriers and Charge Neutrality $n = n_0$ (Equilibrium), $\Delta n(\text{Excess}) = p - n_0$ Δp Charge neutrality light, $\Delta n = \Delta p$ When neutrality is not guaranteed, built-in field causes carrier drift, until neutrality is restored						
Carriers in Action, Drift, Diffusion, Recombination-Generation						
Recombination Lifetime, Photo-detector, Solar Cell, Pulsed Laser						
data-representing electro-optic Modulators						

Asume light generates Δn and Δp . If the light is suddenly turned off, Δn and Δp decay with time until they become zero. The process of decay is called recombination. The time constant of decay is the **recombination time** or **carrier lifetime**, τ . Recombination is nature's way of restoring equilibrium ($\Delta n = \Delta p = 0$)

(contaminants such as Au and Pt. These deep trap capture electrons or holes to facilitate recombination and are called recombination centers. τ is called Recombination Rate [$s^{-1} \cdot cm^{-3}$]. Consider conductivity only $\sigma = q \cdot \mu_n \cdot n = \frac{q \cdot \mu_n}{\tau} \cdot \Delta n \cdot \tau$ (Remember: charge neutrality!) $\tau = \frac{\sigma}{q \cdot \mu_n \cdot \Delta n} = \frac{\sigma}{q \cdot \mu_n \cdot \Delta p}$ **Example:** Photoconductivity

A bar of Si is doped with boron at $[10 \times 10^{15} \text{ cm}^{-3}]$. It is exposed to light such that electron-hole pairs are

very different from n_i^n	Key Parameters	Efficiency [%], Responsivity [A/W], Gain [factor], Bandwidth [f_{3dB}/GHz], Noise [signal to noise ratio, noise equivalent power], Spectral Response, Polarization Dependency	Types of Photodetectors: PIN, NIN, MSM(Photiconductor), APD(Avalanche Photo.Diode)	PhotoConductor	$J_0 = \sigma_0 E = (n_0 q \mu_n + p_0 q \mu_p) E$ With Illumination $\Delta I = \Delta J = A \cdot \Delta \sigma \cdot E = \delta n \cdot q \cdot (\mu_n + \mu_p) \cdot \frac{A}{L}$
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$\eta = G_0 \text{ cm}^{-2} \text{ s}^{-1}$ (generation rate) · τ_n (carrier recombination lifetime) · How much photocurrent do we see $\Delta I = \eta \cdot \left(\frac{q}{e}\right) [\text{mA/W}] \cdot (\text{Photocurrent}) \cdot P_{\text{opt}} [\text{mW}] \cdot (\text{Photocurrent}) \cdot \left(\frac{q}{e}\right) \cdot (\text{Photoconductive gain})$	BJT Analogy to Bi-Polar Transistor base recombination time τ_B transit time τ_t current gain $\beta_F = \frac{\tau_B}{\tau_t}$	3dB Bandwidth - optical bits (Light on/off) Q. How Fast, Q. What's the limitation, Q. What's the light
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x Bandwidth. What do you get? Q: Can we make GB arbitrarily large? $GB = (\frac{e}{h\nu}) (\frac{1}{2\tau})$, $\frac{1}{\tau_e} = \frac{1}{2\tau_p} = \frac{1}{\tau_{ph}}$ = constant for a given device. Gain is achieved at expense of Bandwidth, Its a Figure of Merit (FOM) of Detectors, It can not be made arbitrarily large! Transit time for electron: $\tau_t = \frac{L}{v_{pe}} = \frac{L}{\mu_n E}$. Shot Noise: current is carried by discrete quanta (electron). Random fluctuation in the number of electrons arriving

In a time interval, Δt . The more photons the noiseier ($\sigma_c^2(f) = 2\gamma(f)\Delta t$ Average Current) $\Delta f = f + \Delta f$ SNR = $\frac{f}{\Delta f}$	$\frac{f}{\Delta f}$	Generation and Recombination Noise	Cause: random generation and recombination of carrier in the semiconductor of the Detector ($\sigma_{GR}^2 = \frac{1}{1+2f\tau_{tr}}\Delta f$) Δf The faster the modulation frequency the noisier*, The shorter the transit time and carrier lifetime the noisier*
Thermal ($k_B T$) Noise	Cause: Random thermal motion of charge particles ($\Delta^2 = \frac{4k_B T}{\Delta f}$) Δf The higher the temperature the noisier	Signal to Noise Ratio SNR = $\frac{f^2}{\Delta f}$	Noise Equivalent (NEP) critical power at which SNR = 1 = $\frac{f^2}{\Delta f}$ 1Hz 1Watt! The bandwidth, Detectability D^* ($D^* = \text{RMSD}$), $D^* = \frac{\Delta f \Delta t}{\Delta f \sqrt{2k_B T}}$ Δf also Δf noise bandwidth, Note: NEP = $\frac{1}{D^*}$

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$\alpha \propto \sqrt{\Delta f} / \sqrt{\lambda}$; D^* is a figure of merit (larger is better) **Human eye:** Logarithmic power sensitivity, spectrality (400 – 800 [nm]). Peak sensitivity around (523[nm]) **Silicon Detector:** Linear power sensitivity, Peak sensitivity in infrared (880 [nm]) **Q.** What is the sharp cut-off at longer wavelengths? **Example: Photoconductor** $r_p = \eta \cdot \frac{q}{e} \cdot \left(\frac{P_{opt}}{P_{th}} \right) \cdot \left(\frac{V_{DD}}{2q} + 2q \cdot \frac{V_{DD}}{h\nu} \right) \cdot \sqrt{\Delta f} + \frac{4kT}{e} \Delta f$ **Q.** Do you recognize the different

Q. 5/4. How can we get high SNR in Photon Detector? 1 most desirable, 2 may have long tail in temporal noise (diffusion tail) P and N region can be large E.g material to minimize absorption $\Rightarrow P \sim I - I_N$. Benefits of PIN, small capacitance \Rightarrow smaller RC and higher speed, larger absorption \Rightarrow higher efficiency. But higher transit time \Rightarrow lower speed \Rightarrow Quantum Efficiency: Surface-Illuminated PIN Neglect diffusion current

Waveguide pin $n = n_c(1 - R/(1 - \exp(-\alpha L)))$ Where Γ : Confinement factor | Do edge coupled (waveguide based) detectors have the same $f_{\text{eff}} - n$ trade off? | APD: Avalanche photodiode, biased near reverse breakdown, avalanche, energetic electron (hole) release its kinetic energy by generating an additional electron-hole \rightarrow impact ionization | Usually separate absorption and multiplication (SAM) structure is used for APD.

absorption (InGaAs) (low doping) Multiplication (InP), larger bandgap, higher field (high doping). Ideal case: electron impact ionization only. $\frac{dJ_e}{dx} = \alpha_n J_n(x)$, $J_n(x) = J_n(0) \cdot e^{\alpha_n x}$ At $x = W$ electron current only $J = J_n(x=W) = J_n(0)e^{\alpha_n W} = M_n \cdot J_n(0)$ $M_n = e^{\alpha_n W}$ = Multiplication Factor $\frac{dJ_p}{dx} = \alpha_p J_p(x)$ (Electron current) $= \alpha_n J_n(x)$ (electron impact ionization) $+ \beta_p J_p(x)$ (hole impact ionization) Photocurrent density from absorption

region, Multiplication Factor $M_n = \frac{\omega_n}{\omega_{n0}}$

$$= \frac{1}{\alpha_n \omega_n W} \sin(-(\alpha_n - \beta_n) \tau) = \frac{1}{\alpha_n \omega_n W} \sin(-(\alpha_n - \beta_n) \tau) = \frac{1}{\alpha_n \omega_n W} \sin(-(\alpha_n - \beta_n) \tau)$$

Let $k = \frac{\omega_n}{\omega_{n0}}$, $M_n = \frac{1}{\alpha_n k W}$, $M_n \rightarrow \infty$ at $\alpha_n W = 1 \rightarrow$ unstable $k < 1$ Stable gain with lower noise

APD - GB Product

Response Time $\tau = \tau_i$ (transit time in absorption) + τ_m (multiplication time) $\tau_m \approx \frac{1}{\alpha_n}$ and $\frac{1}{\alpha_n} \approx \frac{1}{\alpha_{n0}}$ when $M_n > 1$ $\tau_i \approx \tau_m$ if τ_i is small

Gain-bandwidth product

$$G_{2\pi} B_{\nu} = M_{\nu} \times \left(\frac{1}{\tau_{\text{APD}}} + \frac{1}{\tau_{\text{Noise}}} \right) = M_{\nu} \times \frac{1}{\tau_{\text{APD}}} \frac{1}{\frac{\tau_{\text{APD}}}{\tau_{\text{Noise}}} + 1} = \frac{1}{\tau_{\text{APD}}} = \text{constant} \quad \text{APD} + \text{Noise} \quad SNR = \frac{\tau_{\text{APD}}^2}{(\tau_{\text{APD}}^2 + \tau_{\text{Noise}}^2)} = \frac{\tau_{\text{APD}}^2 (M_{\nu}^2)^2}{\tau_{\text{APD}}^2 (M_{\nu}^2)^2 + \tau_{\text{Noise}}^2 (M_{\nu}^2)^2} = \frac{\tau_{\text{APD}}^2}{\tau_{\text{APD}}^2 + \tau_{\text{Noise}}^2} \propto \tau_{\text{APD}}^2 \quad \text{For small } \tau_{\text{APD}} : SNR \rightarrow \frac{\tau_{\text{APD}}^2 (M_{\nu}^2)^2}{\tau_{\text{Noise}}^2 (M_{\nu}^2)^2} \propto \tau_{\text{APD}}^2 \quad \text{For large } \tau_{\text{APD}} : SNR \rightarrow \frac{\tau_{\text{APD}}^2}{2\tau_{\text{Noise}}^2} \propto \tau_{\text{APD}} \quad \text{detectors } \lambda > 100 \mu\text{m}$$

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$h\nu = 2E_F = 2\hbar V_F \sqrt{\frac{m}{2}} \sqrt{n + v_0} \left(\frac{e \phi(x)}{2k_B T} \right)^{1/2} - v_0 = v = \sqrt{\frac{e \phi(x)}{(20.5 \times 10^{-10})^2 (10.9 \times 10^{18} \text{ [cm}^{-3}\text{)])^2}}}$, $\gamma = \frac{1}{2 \times 10^{18} \text{ cm}^{-3} \sqrt{v}}$, $= 5.19 \text{ V} = |v| + (-0.8 \text{ V})$, $v_d = -4.39$ and $= 5.99$. **Advantages found in a graphene based waveguide** modulator in the practice problem. The size of the modulator is determined by the distinct advantages found in a graphene based waveguide-integrated electro-absorption modulator. [1]. Strong line graphene interaction, in

comparison to compound semiconductors, such as those exhibiting the quantum-well band quantum-confined (QCSE), a monolayer of graphene possesses a much stronger inter-band optical transition, which finds applications in novel photodetectors. [2] Broadband operation, as the high frequency dynamic conductivity Dirac fermions is constant, the optical absorption of graphene is independent of wavelength, covering all telecommunications bands and also mid- and far infrared [3]. High speed operation which a carrier mobility exceeding $200\text{ cm}^2\text{ V}^{-1}\text{ s}^{-1}$ at room temperature the fermi level and hence the optical absorption of graphene can be rapidly modulated by the band-filling effect. In addition, speed limiting processes in graphene operate on the timescales of picoseconds which implies that graphene - based electronics may have the

the product of resistance and capacitance (RC). Due to manufacturing constraints lower the resistance is therefore a preferred approach for scaling performance. ^[2] In the vertical dimension, solutions are aimed at minimizing internal resistance. ^[3] In the lateral dimension, solutions are aimed at optimizing the conductivity of the metal forming the wire. ^[3] ^[4] ^[5] ^[6] ^[7] ^[8] ^[9] ^[10] ^[11] ^[12] ^[13] ^[14] ^[15] ^[16] ^[17] ^[18] ^[19] ^[20] ^[21] ^[22] ^[23] ^[24] ^[25] ^[26] ^[27] ^[28] ^[29] ^[30] ^[31] ^[32] ^[33] ^[34] ^[35] ^[36] ^[37] ^[38] ^[39] ^[40] ^[41] ^[42] ^[43] ^[44] ^[45] ^[46] ^[47] ^[48] ^[49] ^[50] ^[51] ^[52] ^[53] ^[54] ^[55] ^[56] ^[57] ^[58] ^[59] ^[60] ^[61] ^[62] ^[63] ^[64] ^[65] ^[66] ^[67] ^[68] ^[69] ^[70] ^[71] ^[72] ^[73] ^[74] ^[75] ^[76] ^[77] ^[78] ^[79] ^[80] ^[81] ^[82] ^[83] ^[84] ^[85] ^[86] ^[87] ^[88] ^[89] ^[90] ^[91] ^[92] ^[93] ^[94] ^[95] ^[96] ^[97] ^[98] ^[99] ^[100] ^[101] ^[102] ^[103] ^[104] ^[105] ^[106] ^[107] ^[108] ^[109] ^[110] ^[111] ^[112] ^[113] ^[114] ^[115] ^[116] ^[117] ^[118] ^[119] ^[120] ^[121] ^[122] ^[123] ^[124] ^[125] ^[126] ^[127] ^[128] ^[129] ^[130] ^[131] ^[132] ^[133] ^[134] ^[135] ^[136] ^[137] ^[138] ^[139] ^[140] ^[141] ^[142] ^[143] ^[144] ^[145] ^[146] ^[147] ^[148] ^[149] ^[150] ^[151] ^[152] ^[153] ^[154] ^[155] ^[156] ^[157] ^[158] ^[159] ^[160] ^[161] ^[162] ^[163] ^[164] ^[165] ^[166] ^[167] ^[168] ^[169] ^[170] ^[171] ^[172] ^[173] ^[174] ^[175] ^[176] ^[177] ^[178] ^[179] ^[180] ^[181] ^[182] ^[183] ^[184] ^[185] ^[186] ^[187] ^[188] ^[189] ^[190] ^[191] ^[192] ^[193] ^[194] ^[195] ^[196] ^[197] ^[198] ^[199] ^[200] ^[201] ^[202] ^[203] ^[204] ^[205] ^[206] ^[207] ^[208] ^[209] ^[210] ^[211] ^[212] ^[213] ^[214] ^[215] ^[216] ^[217] ^[218] ^[219] ^[220] ^[221] ^[222] ^[223] ^[224] ^[225] ^[226] ^[227] ^[228] ^[229] ^[230] ^[231] ^[232] ^[233] ^[234] ^[235] ^[236] ^[237] ^[238] ^[239] ^[240] ^[241] ^[242] ^[243] ^[244] ^[245] ^[246] ^[247] ^[248] ^[249] ^[250] ^[251] ^[252] ^[253] ^[254] ^[255] ^[256] ^[257] ^[258] ^[259] ^[260] ^[261] ^[262] ^[263] ^[264] ^[265] ^[266] ^[267] ^[268] ^[269] ^[270] ^[271] ^[272] ^[273] ^[274] ^[275] ^[276] ^[277] ^[278] ^[279] ^[280] ^[281] ^[282] ^[283] ^[284] ^[285] ^[286] ^[287] ^[288] ^[289] ^[290] ^[291] ^[292] ^[293] ^[294] ^[295] ^[296] ^[297] ^[298] ^[299] ^[300] ^[301] ^[302] ^[303] ^[304] ^[305] ^[306] ^[307] ^[308] ^[309] ^[310] ^[311] ^[312] ^[313] ^[314] ^[315] ^[316] ^[317] ^[318] ^[319] ^[320] ^[321] ^[322] ^[323] ^[324] ^[325] ^[326] ^[327] ^[328] ^[329] ^[330] ^[331] ^[332] ^[333] ^[334] ^[335] ^[336] ^[337] ^[338] ^[339] ^[340] ^[341] ^[342] ^[343] ^[344] ^[345] ^[346] ^[347] ^[348] ^[349] ^[350] ^[351] ^[352] ^[353] ^[354] ^[355] ^[356] ^[357] ^[358] ^[359] ^[360] ^[361] ^[362] ^[363] ^[364] ^[365] ^[366] ^[367] ^[368] ^[369] ^[370] ^[371] ^[372] ^[373] ^[374] ^[375] ^[376] ^[377] ^[378] ^[379] ^[380] ^[381] ^[382] ^[383] ^[384] ^[385] ^[386] ^[387] ^[388] ^[389] ^[390] ^[391] ^[392] ^[393] ^[394] ^[395] ^[396] ^[397] ^[398] ^[399] ^[400] ^[401] ^[402] ^[403] ^[404] ^[405] ^[406] ^[407] ^[408] ^[409] ^[410] ^[411] ^[412] ^[413] ^[414] ^[415] ^[416] ^[417] ^[418] ^[419] ^[420] ^[421] ^[422] ^[423] ^[424] ^[425] ^[426] ^[427] ^[428] ^[429] ^[430] ^[431] ^[432] ^[433] ^[434] ^[435] ^[436] ^[437] ^[438] ^[439] ^[440] ^[441] ^[442] ^[443] ^[444] ^[445] ^[446] ^[447] ^[448] ^[449] ^[450] ^[451] ^[452] ^[453] ^[454] ^[455] ^[456] ^[457] ^[458] ^[459] ^[460] ^{[4}

approaching Q.E. of 80% contact pad length: $l = 0.5 \mu\text{m}$ bias voltage: $V_2 = 1[\text{V}]$ mobility: average of n and p-type for a doping level of 10^{17} cm^{-3} room temperature 300k hll $N_A = N_D$ $n = N_D$ $p = N_A$ photodetector gain S ; Carrier lifetime: $\tau_{tr} =$ gain of photodetector $\Delta I =$ number of photons χ charge \times gain $V = \frac{1}{2} \left[\epsilon = -\frac{d\phi}{dx} \right]$ $\tau_{tr} = \frac{d}{v_d}$ $\epsilon = -\frac{1}{2}$ transit time $\tau_t = \frac{d}{v_d} = \frac{d}{\mu E} = \frac{d^2}{\mu V} \left[\tilde{S} i = \mu - \frac{p_{tr} v_d}{2} \right] J = \frac{1}{2}$

[illegible]

gain = 0.1909771 very little gain [c] $\Delta I = \frac{\text{photon}}{\text{electron}}$ - charge - gain [QE = 0.9] $P = 1.0 \times 10^{-7} [\text{W}]$ $I = 1.1 \times 10^{-16} [\text{W}]$ $P = 1.0 \times 10^{-3} [\text{W}]$ $I = 1.31 \times 10^{-6} [\text{m}]$ $\Delta = \eta \left(\frac{1}{P_{\text{opt}}} \left(\frac{1}{\tau_c} \right) \right)$ τ_c = carrier lifetime [s] τ_m = transit time [s] $h\nu$ = energy of a photon $E = h\nu$ $E = \frac{h}{\lambda}$ $= \frac{6.626 \times 10^{-34} \times (2.998 \times 10^8 \text{ m/s})}{1.31 \times 10^{-6}}$ $E = 1.51 \times 10^{-19} [\text{J}] = h\nu$ η = quantum efficiency $\Delta I = 0.9 \left(\frac{1.51 \times 10^{-19}}{1.156 \times 10^{-16}} \right) \times (1.0 \times 10^{-3}) (0.19) = 0.00018 [\text{A}]$

Hint When light moves from a medium to a different medium we have on of three phenomena, **refraction**, when the light bounces off the medium. **Absorption**, when the light is converted to another form of energy. **Transmission**, when light passes through the medium. **Refraction**, change in direction due to a change in transmission medium. **Phase velocity**, rate at which the phase of the wave propagates in space.

velocity at which the wave of any one frequency component of the wave travels. **group velocity**, velocity at which the overall shape of the waves amplitude, known as the modulation or envelope of the wave, propagates through space. **Wave equation in 3D**, $\nabla^2 \psi = \frac{1}{c^2} \frac{\partial^2 \psi}{\partial t^2}$ **Maxwells equation in differential form**: **Gauss's law for electric**, $\nabla \cdot \mathbf{E} = \frac{\rho}{\epsilon_0}$ **Gauss's law for magnetism**, $\nabla \cdot \mathbf{B} = 0$ **Faraday equation**, $\nabla \times \mathbf{E} = -\frac{\partial \mathbf{B}}{\partial t}$

couplers: have variable coupling between the two transmission lines. These couplers can have quite wide bandwidth, greater than 28:1 **Best Coupling:** $n_{T1M} + n_{T2M} = 2n_{T3M}$ **Cross:** $n_{T2M} \neq n_{T3M}$ **bar:** $n_{T1M} = n_{T2M}$ **Laser Analysis:** $\alpha_i = 20\text{cm}^{-1}$ $\Gamma = 20\%$ $L = 100\text{ }\mu\text{m}$ $\eta_i = 3.9766$ $R = 40\%$ **Intrinsic loss:** $\alpha_i[\text{cm}^{-1}]$ **Overlap factor:** Γ **laser length:** $L[\mu\text{m}]$ **gain medium index of refraction:** η **reflection:** R **threshold**

$$\alpha_{\text{eff}} = \frac{1}{2} \ln \left[\frac{\Gamma(1 + \frac{1}{2})}{\Gamma(\frac{1}{2})} \right] = -0.1967$$

Within a discrete set of energy substances. Only a discrete set of frequencies may be absorbed or emitted by the system. **When an external electric field is applied, the electron states shift to lower energies while the hole states shift to higher energies. This reduces the permitted light absorption or emission frequencies. Additionally, the external electric field shifts electrons and holes to opposite sides of the well, decreasing the overlap**

[illegible]